FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT IN AN APPLICATION	DOCKET NO: 007352 USA/ETCH/DRIE/JB	APPLICATION NO.: 10/615,159
	APPLICANT: Frum et al.	
	FILING DATE: 7/7/2003	GROUP ART UNIT: 1763

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS	FILING DATE IF APPROPRIATE
GRG	5,450,205	09/12/1995	Sawin, et al.			
	5,500,373	04/02/1996	Maung, et al.			
	5,566,308	10/15/1996	Bobel, et al.			
	5,658,418	08/19/1997	Coronel, et al.			
	5,746,874	05/26/1998	Ye, et al.			
	6,083,344	06/27/2000	Grimbergen, et al.			
	6,165,311	12/26/2000	Collins, et al.			
	4,147,435	04/30/1979	Habegger			
	4,869,281	07/11/1989	Dolins, et al.			
GRG	4,869,772	07/11/1989	Bama, et al.			

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION YES	TRANSLATION NO

OTHER DOCUMENTS (*Including Author, Title, Date, Pertinent Pages, etc.*)

GRG	Maynard, et al., "Multiwavelength Ellipsometry for Real-time Process Control of the Plasma Etching of Patterned Samples." J. Vac Sci Technol. B, 15 (1), Jan/Feb 1997, pages 109-115 ✓
GRG	Klemens, F.P., et al., "High Density Plasma Gate Etching of 0.12 μm Devices with Sub 1.5 nm Gate-Oxides." Electrochemical Society Proceedings, Volume 97-30, pages 85-95

EXAMINER	George Goudreau	DATE CONSIDERED	5-04

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.